

Supporting Information

On the Electron-Induced Reactions of $(\text{CH}_3)_3\text{AuP}(\text{CH}_3)_3$: A Combined UHV Surface Science and Gas-Phase Study

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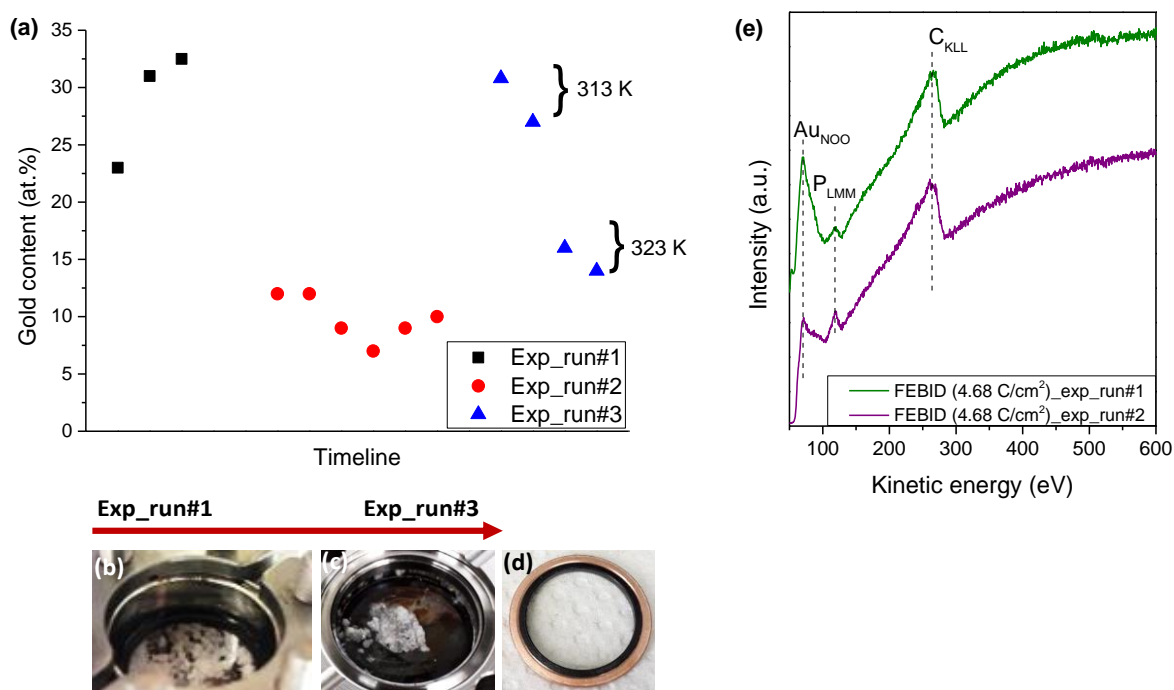


Figure S1. (a) Gold content of FEBID deposits on SiO_2 (230 nm)/ $\text{Si}(111)$ substrate over the timeline of three consecutive experiment runs. Between experiment-run#1 and -run#2 is a pause of three days, and between run#2 and run#3 is one day. (b) The color of freshly filled $(\text{CH}_3)_3\text{AuP}(\text{CH}_3)_3$ precursor, and (c) the color of the precursor at the end of experiment-run#3. (d) The color change on copper sealing after the experiment run#3. (e) AES results obtained from the experiments run#1 and run#2.